

Timo Hatanp

List of Publications by Year in Descending Order

Source: <https://exaly.com/author-pdf/8974372/timo-hatanpaa-publications-by-year.pdf>

Version: 2024-04-10

This document has been generated based on the publications and citations recorded by exaly.com. For the latest version of this publication list, visit the link given above.

The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

51 papers	1,380 citations	23 h-index	36 g-index
54 ext. papers	1,531 ext. citations	5.6 avg, IF	4.22 L-index

#	Paper	IF	Citations
51	Highly Material Selective and Self-Aligned Photo-assisted Atomic Layer Deposition of Copper on Oxide Materials. <i>Advanced Materials Interfaces</i> , 2021 , 8, 2100014	4.6	3
50	Novel electroblowing synthesis of tin dioxide and composite tin dioxide/silicon dioxide submicron fibers for cobalt(ii) uptake.. <i>RSC Advances</i> , 2021 , 11, 15245-15257	3.7	0
49	Highly conductive and stable CoS thin films by atomic layer deposition: from process development and film characterization to selective and epitaxial growth. <i>Dalton Transactions</i> , 2021 , 50, 13264-13275	4.3	
48	Atomic Layer Deposition of Nickel Nitride Thin Films using NiCl ₂ (TMPDA) and Tert-Butylhydrazine as Precursors. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2019 , 216, 1900058	1.6	4
47	Crystalline tungsten sulfide thin films by atomic layer deposition and mild annealing. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 020921	2.9	10
46	Submicron fibers as a morphological improvement of amorphous zirconium oxide particles and their utilization in antimonate (Sb(v)) removal.. <i>RSC Advances</i> , 2019 , 9, 22355-22365	3.7	6
45	Nickel Germanide Thin Films by Atomic Layer Deposition. <i>Chemistry of Materials</i> , 2019 , 31, 5314-5319	9.6	5
44	Novel electroblowing synthesis of submicron zirconium dioxide fibers: effect of fiber structure on antimony(V) adsorption. <i>Nanoscale Advances</i> , 2019 , 1, 4373-4383	5.1	9
43	Atomic layer deposition of cobalt(II) oxide thin films from Co(BTSA) ₂ (THF) and H ₂ O. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2019 , 37, 010908	2.9	1
42	Atomic Layer Deposition of PbI ₂ Thin Films. <i>Chemistry of Materials</i> , 2019 , 31, 1101-1109	9.6	34
41	Atomic Layer Deposition of Intermetallic Co ₃ Sn ₂ and Ni ₃ Sn ₂ Thin Films. <i>Advanced Materials Interfaces</i> , 2019 , 6, 1801291	4.6	8
40	Diamine Adduct of Cobalt(II) Chloride as a Precursor for Atomic Layer Deposition of Stoichiometric Cobalt(II) Oxide and Reduction Thereof to Cobalt Metal Thin Films. <i>Chemistry of Materials</i> , 2018 , 30, 3499-3507 ²¹	9.6	21
39	Intralanthanide Separation on Layered Titanium(IV) Organophosphate Materials via a Selective Transmetalation Process. <i>ACS Applied Materials & Interfaces</i> , 2018 , 10, 22083-22093	9.5	18
38	Studies on Thermal Atomic Layer Deposition of Silver Thin Films. <i>Chemistry of Materials</i> , 2017 , 29, 2040-2045	9.45	23
37	Potential gold(I) precursors evaluated for atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 01B112	2.9	13
36	Atomic layer deposition of tin oxide thin films from bis[bis(trimethylsilyl)amino]tin(II) with ozone and water. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 041506	2.9	12
35	Atomic Layer Deposition of Crystalline MoS ₂ Thin Films: New Molybdenum Precursor for Low-Temperature Film Growth. <i>Advanced Materials Interfaces</i> , 2017 , 4, 1700123	4.6	75

34	Titanium alkylphosphate functionalised mesoporous silica for enhanced uptake of rare-earth ions. <i>Journal of Materials Chemistry A</i> , 2017 , 5, 23805-23814	13	12
33	Thermal Atomic Layer Deposition of Continuous and Highly Conducting Gold Thin Films. <i>Chemistry of Materials</i> , 2017 , 29, 6130-6136	9.6	25
32	Bismuth iron oxide thin films using atomic layer deposition of alternating bismuth oxide and iron oxide layers. <i>Thin Solid Films</i> , 2016 , 611, 78-87	2.2	16
31	Electric and Magnetic Properties of ALD-Grown BiFeO ₃ Films. <i>Journal of Physical Chemistry C</i> , 2016 , 120, 7313-7322	3.8	25
30	Alkylsilyl compounds as enablers of atomic layer deposition: analysis of (Et ₃ Si) ₃ As through the GaAs process. <i>Journal of Materials Chemistry C</i> , 2016 , 4, 449-454	7.1	2
29	(Et ₃ Si) ₂ Se as a precursor for atomic layer deposition: growth analysis of thermoelectric Bi ₂ Se ₃ . <i>Journal of Materials Chemistry C</i> , 2015 , 3, 4820-4828	7.1	12
28	Atomic layer deposition and characterization of Bi ₂ Te thin films. <i>Journal of Physical Chemistry A</i> , 2015 , 119, 2298-306	2.8	23
27	Magnetic Properties of Polycrystalline Bismuth Ferrite Thin Films Grown by Atomic Layer Deposition. <i>Journal of Physical Chemistry Letters</i> , 2014 , 5, 4319-23	6.4	21
26	Bismuth(III) Alkoxide Catalysts for Ring-Opening Polymerization of Lactides and γ -Caprolactone. <i>Macromolecular Chemistry and Physics</i> , 2013 , 214, 707-715	2.6	9
25	Precursors as enablers of ALD technology: Contributions from University of Helsinki. <i>Coordination Chemistry Reviews</i> , 2013 , 257, 3297-3322	23.2	63
24	Programming nanostructured soft biological surfaces by atomic layer deposition. <i>Nanotechnology</i> , 2013 , 24, 245701	3.4	25
23	Cycloheptatrienyl-Cyclopentadienyl Heteroleptic Precursors for Atomic Layer Deposition of Group 4 Oxide Thin Films. <i>Chemistry of Materials</i> , 2012 , 24, 2002-2008	9.6	22
22	Study of amorphous lithium silicate thin films grown by atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012 , 30, 01A106	2.9	35
21	Lithium Phosphate Thin Films Grown by Atomic Layer Deposition. <i>Journal of the Electrochemical Society</i> , 2012 , 159, A259-A263	3.9	77
20	Iridium metal and iridium oxide thin films grown by atomic layer deposition at low temperatures. <i>Journal of Materials Chemistry</i> , 2011 , 21, 16488		39
19	Effects of spray drying on physicochemical properties of chitosan acid salts. <i>AAPS PharmSciTech</i> , 2011 , 12, 637-49	3.9	50
18	The use of disaccharides in inhibiting enzymatic activity loss and secondary structure changes in freeze-dried β -galactosidase during storage. <i>Pharmaceutical Research</i> , 2011 , 28, 540-52	4.5	22
17	Crystal structures and thermal properties of some rare earth alkoxides with tertiary alcohols. <i>Journal of Thermal Analysis and Calorimetry</i> , 2011 , 105, 61-71	4.1	5

16	(MeCp)Ir(Chd) and molecular oxygen as precursors in atomic layer deposition of iridium. <i>Journal of Materials Chemistry</i> , 2010 , 20, 7669		32
15	In Situ Reaction Mechanism Studies on Atomic Layer Deposition of Sb ₂ Te ₃ and GeTe from (Et ₃ Si) ₂ Te and Chlorides. <i>Chemistry of Materials</i> , 2010 , 22, 1386-1391	9.6	46
14	Study of bismuth alkoxides as possible precursors for ALD. <i>Dalton Transactions</i> , 2010 , 39, 3219-26	4.3	37
13	Atomic Layer Deposition of Materials for Phase-Change Memories. <i>ECS Transactions</i> , 2009 , 25, 399-407	1	17
12	Atomic layer deposition of Ge ₂ Sb ₂ Te ₅ thin films. <i>Microelectronic Engineering</i> , 2009 , 86, 1946-1949	2.5	58
11	Atomic layer deposition of metal tellurides and selenides using alkylsilyl compounds of tellurium and selenium. <i>Journal of the American Chemical Society</i> , 2009 , 131, 3478-80	16.4	132
10	Alkylsilyl Compounds of Selenium and Tellurium: New Precursors for ALD. <i>ECS Transactions</i> , 2009 , 25, 609-616	1	13
9	Study of a novel ALD process for depositing MgF ₂ thin films. <i>Journal of Materials Chemistry</i> , 2007 , 17, 5077		59
8	Crystal structures and thermal properties of Ba(1,2,4-t-Bu ₃ C ₅ H ₂) ₂ and Sr(1,2,4-t-Bu ₃ C ₅ H ₂) ₂ : Precursors for atomic layer deposition. <i>Journal of Organometallic Chemistry</i> , 2007 , 692, 5256-5262	2.3	25
7	Atomic Layer Deposition of Ferroelectric Bismuth Titanate Bi ₄ Ti ₃ O ₁₂ Thin Films. <i>Chemistry of Materials</i> , 2006 , 18, 3883-3888	9.6	43
6	Scale-up of the BaTiO ₃ ALD Process onto 200 mm Wafer. <i>ECS Transactions</i> , 2006 , 1, 137-141	1	8
5	Synthesis and characterisation of cyclopentadienyl complexes of barium: precursors for atomic layer deposition of BaTiO ₃ . <i>Dalton Transactions</i> , 2004 , 1181-8	4.3	47
4	Bismuth precursors for atomic layer deposition of bismuth-containing oxide films. <i>Journal of Materials Chemistry</i> , 2004 , 14, 3191-3197		71
3	Ancillary ligand effect on the properties of "Mg(thd) ₂ " and crystal structures of [Mg(thd) ₂ (ethylenediamine)] ₂ , [Mg(thd) ₂ (tmeda)], and [Mg(thd) ₂ (trien)]. <i>Inorganic Chemistry</i> , 2001 , 40, 788-94	5.1	22
2	Properties of [Mg ₂ (thd) ₄] as a Precursor for Atomic Layer Deposition of MgO Thin Films and Crystal Structures of [Mg ₂ (thd) ₄] and [Mg(thd) ₂ (EtOH) ₂]. <i>Chemistry of Materials</i> , 1999 , 11, 1846-1852	9.6	44
1	Molecular Layer Deposition of Thermally Stable Polybenzimidazole-Like Thin Films and Nanostructures. <i>Advanced Materials Interfaces</i> , 2003 , 7, 2200370	4.6	